





SENTECH Thin Film Metrology Seminar and Workshop

Thin Film Metrology Seminar

Date: On Wednesday, 29th November 2023

Host: SENTECH Gesellschaft für Sensortechnik mbH, Konrad-Zuse-Bogen 13, 82152 Krailling
Location: SENTECH Instruments GmbH, Entrance: Johann-Hittorf-Str./James-Franck-Str., 12489 Berlin

Networking dinner: At Wandel Restaurant, Eisenhutweg 118, 12489 Berlin-Adlershof

SEMINAR PROGRAM:

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Pos.	Time	Talk
1.	9:00	Welcome and SENTECH thin film metrology products Friedrich P. Witek, SENTECH GmbH, Krailling and SENTECH Instruments GmbH, Berlin
2.	9:15	Process control and monitoring of optical microsensors Christian Möller, CiS Forschungsinstitut für Mikrosensorik GmbH, Erfurt
3.	9:45	Quality control on SiC, Si and transparent substrates by SENDURO MEMS Sven Peters, SENTECH Instruments GmbH, Berlin
4.	10:15	Recent activities in in-situ ellipsometry and spectroscopy on optical coatings Michael Vergöhl, Fraunhofer Insitute for Surface Engineering and Thin Films (IST), Braunschweig
	10:45	Coffee Break
5.	11:15	Spectroscopic ellipsometry and Mueller matrix ellipsometry for the analysis of anisotropic materials and 2D periodic structures (scatterometry) Alexander Treffer, SENTECH Instruments GmbH, Berlin
6.	11:45	Ellipsometric Characterisation of ALD-Heterostructures Dr. Adriana Szeghalmi, Fraunhofer Institute for Applied Optics and Precision Engineering IOF, Jena
	12:15	Lunch break
7.	13:45	Tackling challenges in ellipsometry: low specular reflectance, inhomogeneous indices, and beyond Sangam Chatterjee, Justus-Liebig Universität Giessen, Giessen
8.	14:15	Ellipsometry for quality control in device packaging Uwe Richter, SENTECH Instruments GmbH, Berlin
9.	14:35	Ellipsometry for mid infrared applications Valentin Wittwer, University Neuchâtel, Institute for Physics, Neuchâtel, Switzerland
	15:05	Coffee Break
10.	15:45	Quality control on 300 mm wafers using SENresearch 4.0 Sven Peters, SENTECH Instruments GmbH, Berlin
	16:05	End of Seminar. Everyone is kindly invited to visit the SENTECH Thin Film Metrology Application Laboratory.
	19:00	Networking dinner at Wandel Restaurant, Eisenhutweg 118, 12489 Berlin-Adlershof







Thin Film Metrology Workshop

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WORKSHOP PROGRAM:

Pos.	Time	Event
1.	9:00	Introduction into spectroscopic ellipsometry – Complex sample analysis in a wide spectral range from DUV to NIR Alexander Treffer, SENTECH Instruments GmbH, Berlin
2.	9:50	How to recognise and push limits in spectroscopic ellipsometry Sven Peters, SENTECH Instruments GmbH, Berlin
	10:40	Coffee Break
3.	11:00	First Block of Workshops
	12:10	Lunch Break
4.	13:30	Second Block of Workshops
5.	14:40	Third Block of Workshops
	15:40	Coffee Break
6.	16:00	Fourth Block of Workshops
	17:00	End of Workshops

Please choose four topics in advance and notify us with your registration for the Workshop. This will help in advance with distributing everyone accordingly into teams of eight maximum. You will find the topics on the next page. If you are interested in Topic 3 and want to bring your own sample, check corresponding box.

Extra Notice:

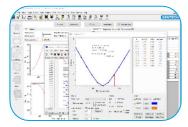
Please take care not to bring confidential samples or samples under NDA for the Workshop "Live measurements of customer samples on SENDIRA and SENresearch" as these measurements are done in groups.







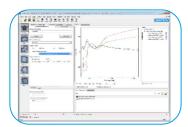
Topics:



 Programming of scripts for spectroscopic ellipsometry for automation and integration of external hardware

With Uwe Richter

Location: Presentation room



2. Workflow of spectroscopic ellipsometry with SpectraRay/4 - introduction to advanced operation

With Alexander Treffer

Location: Conference room



3. Live measurements of customer samples on SENDIRA and SENresearch 4.0

With Sven Peters

Location: Metrology Application Laboratory, Main Room



4. Automation of spectroscopic ellipsometry in production, SENDURO MEMS

With Georg Ditmar

Location: Metrology Application Laboratory, Automation Room



5. Benefits of reflectometry adding to ellipsometry for small spot size, fast mapping and trough silicon via (TSV) analysis

With Johanna Reck

Location: Metrology Application Laboratory, Entrance Room



6. How to apply in-situ metrology for plasma processing

With Marco Volleth and Jakob Zessin

Location: Plasma Application Laboratory